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	Application No.	Applicant(s)	•
Notice of Allowability	10/657,168	ANGELOPOULOS	ET AL.
	Examiner	Art Unit	
	Rosemary E. Ashton	1752	
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI-	(OR REMAINS) CLOSED in this ap or other appropriate communication GHTS. This application is subject to and MPEP 1308.	pplication. If not include the mailed in due	ded Course THIS
1. This communication is responsive to the paper filed 9 September 5	<u>ember 2003</u> .		
2. The allowed claim(s) is/are <u>34-51</u> .			
3. The drawings filed on are accepted by the Examiner			
 4. ☐ Acknowledgment is made of a claim for foreign priority unda) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	been received. been received in Application No	- 	ation from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONMETHIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a reply ENT of this application.	complying with the re	quirements
 A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which gives 	tted. Note the attached EXAMINER s reason(s) why the oath or declara	'S AMENDMENT or Nation is deficient.	NOTICE OF
 CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftsperso 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1.8 each sheet. Replacement sheet(s) should be labeled as such in the depos attached Examiner's comment regarding REQUIREMENT F 	Amendment / Comment or in the Comment or in the Comment or in the drawing to 37 CFR 1.121(c) it of BIOLOGICAL MATERIAL r	Office action of ngs in the front (not the d).	-
 Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date 9/9/03 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material 	5. ☐ Notice of Informal P 6. ☐ Interview Summary Paper No./Mail Dat 7. ☒ Examiner's Amendn 8. ☒ Examiner's Stateme 9. ☐ Other	(PTO-413), e nent/Comment	

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EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

2. The following is an examiner's statement of reasons for allowance: The prior art does not teach a patterning method using a resist composition as shown below. Step (d) requires the resist to be a negative resist as the unexposed portions of the resist composition are removed. While the method is taught in JP 5-181280, cited on applicant's IDS, using a resist composition comprising a polysilane polymer having fused aryl groups, the composition in JP '280 is positive acting as shown in section 10 of the English translation were it states "...as a resist of the positive type by which dissolution removal of the energy line exposure part...". The composition also does not have a crosslinker.

34. (New) A method of forming a patterned material layer on a substrate, the method comprising:

- (a) providing a substrate having a material layer on a surface,
- (b) providing a layer of resist over said material layer, said resist comprising:
- (i) a silicon-containing polymer with pendant fused moieties selected from the group consisting of fused aliphatic moieties, homocyclic fused aromatic moieties, and heterocyclic fused aromatic moieties and sites for reaction with a crosslinking agent,
 - (ii) an acid-sensitive crosslinking agent, and
 - (iii) a radiation-sensitive acid generator,
 - (c) patternwise exposing the resist layer to imaging radiation,
- (d) removing portions of the resist layer not exposed in step (c) to create spaces in said resist layer corresponding to said pattern,
- (e) removing portions of the material layer at said spaces formed in step (d).

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Kitakohji et al U.S. patent no. 4,600,685 teaches a patterning method using a negative resist

composition comprising a polysilsesquioxane polymer, however, the composition does not have a

crosslinker or a radiation-sensitive generator.

Any comments considered necessary by applicant must be submitted no later than the payment

of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such

submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

3. Any inquiry concerning this communication or earlier communications from the examiner should

be directed to Rosemary E. Ashton whose telephone number is 571-272-1326. The examiner works a 6

hr. daily work schedule and can normally be reached M-F between 10:00 am and 4:00 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

Cynthia Kelly can be reached at 571-272-1526.

The fax phone number for the organization where this application or proceeding is assigned is

703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application

Information Retrieval (PAIR) system. Status information for published applications may be obtained from

either Private PAIR or Public PAIR. Status information for unpublished applications is available through

Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC)

at 866-217-9197 (toll-free).

Alfalta

Rosemary E. Ashton Primary Examiner Art Unit 1752 Page 3

rea August 1, 2004

ROSEMARY ASHTON PRIMARY EXAMINER